

ABSTRACT

Provided is a polishing slurry that can more efficiently obtain a polished surface with good surface characteristics at a high polishing rate even for polishing targets with relatively low mechanical strength. The polishing slurry contains α -alumina as abrasive particles in an aqueous medium, wherein the α -alumina has an average particle diameter (D50) of 80 to 120 nm at a volume-based cumulative value of 50% in a particle size distribution determined by a laser diffraction scattering method, a specific surface area (BET) measured in accordance with JIS-Z8830 (2013) of 20 m²/g or more, and a ratio (BET/D50) of the specific surface area (BET) to the average particle diameter (D50) of $1.5 \text{ m/g} \times 10^{-4}$ or more.